PATENT ABSTRACTS OF JAPAN

(11)Publication number:

09-078267

(43) Date of publication of application: 25.03.1997

(51)Int.CI.

C23F 4/00 C23C 16/50 H01L 21/205 H01L 21/304

(21)Application number: 07-264675

(71)Applicant: EBARA CORP

(22)Date of filing:

20.09.1995

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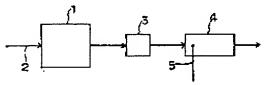
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(54) DETECTING METHOD FOR END POINT IN CLEANING PROCESS FOR THIN FILM FORMING DEVICE WITH CHLORINE TRIFLUORIDE

(57)Abstract:

PROBLEM TO BE SOLVED: To accurately detect the end point of cleaning in a cleaning process in a thin film forming device with CIF3.

SOLUTION: In the cleaning process of a thin film deposited in a thin film forming device 1 by using CIF3, the waste cleaning gas discharged from the thin film forming device 1 is introduced to an adsorbent tank 4 filled with an adsorbent such as iron oxide. By measuring (5) temp. changes in the adsorbent tank, the end point of the cleaning process is monitored. Thereby, the process can be easily and accurately monitored.



LEGAL STATUS

[Date of request for examination]

16.10.1997

[Date of sending the examiner's decision of rejection]

Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

3056675

[Date of registration]

14.04.2000

[Number of appeal against examiner's decision

of rejection]

(19)日本国特許庁 (JP) (12) 公開特許公報(A)

(11)特許出願公開番号

特開平9-78267

(43)公開日 平成9年(1997)3月25日

(全 3 頁)			
0239			
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(57)【要約】

【課題】 薄膜形成装置のCIF3 によるクリーニング において、クリーニングの終点を正確に検知する。

【解決手段】 薄膜形成装置1内に堆積した薄膜のC1 F3 を用いるクリーニングにおいて、前記薄膜形成装置 1から排出するクリーニング排ガスを鉄酸化物等の吸着 剤を充てんした吸着剤槽4に導入し、該吸着剤槽に生じ る温度変化を測定5することにより前記クリーニングの 終点をモニターすることによる。

